SLOT B

APJ ABDUL KALAM TECHNOLOGICAL UNIVERSITY FIRST SEMESTER M.TECH DEGREE EXAMINATION, APR 2021/DEC 2021

Branch: Electronics & Communication

Stream: VLSI & Embedded Systems

Course Code & Name: 01EC6603 VLSI Technology & Design

Answer *any two full* questions from *each* part Limit answers to the required points.

Max. Marks: 60

Duration: 3 hours

PART A

- 1. a. Obtain the Drain characteristics & Transfer characteristics of n-channel (4.5 marks) Enhancement type MOSFET and explain its regions of operation.
 - b. What is EGS? Explain the production of EGS from Hydrogen reduction (4.5 marks) of TrichloroSilane.
- 2. a. Explain the impact of Channel Length Modulation on Drain Current in (4.5 marks) Saturation region of a MOSFET.
 - b. Give the principle involved in Molecular Beam Epitaxy. Explain MBE (4.5 marks) with a neat schematic of MBE Growth System.
- 3. a. What are Small Geometry Effects? Briefly explain the following Small (4.5 marks) Geometry Effects:

i)Sub threshold Conduction & DIBL ii)Punch through

b. Give short notes on Dry Etching & Wet Chemical Etching. Explain the (4.5 marks) significance of DC and AC Plasma excitation in etching Process.

PART B

- a. Give the significance of the Physical Vapour Deposition methods in IC (4.5 marks) Processing. Explain Sputtering with a neat schematic diagram of sputtering system.
 - b. Explain the functioning of Depletion-mode load NMOS Inverter. Obtain (4.5 marks) the inverter characteristics & specify its limitations.

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| 5. | a. | Give the models of atomic diffusion mechanisms in solids. Derive Fick's 2 nd law of diffusion. | (4.5 marks) |
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| | b. | Explain the two methods by which dynamic power dissipation occurs in CMOS circuits. | (4.5 marks) |

| 6. | a. | Give the significance of below process in Ion Implantaion. | | | (4.5 marks) |
|----|----|--|---------------|--|-------------|
| | | i)Ion Stopping | ii)Channeling | | |

| b. | What is pseudo NMOS logic? Implement the following: | (4.5 marks) |
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- 4 input pseudo NMOS NOR gate 4 input pseudo NMOS NAND gate i) ii)

PART C

| 7. | a. | What is Bistability principle? Give the transistor level implementation of a CMOS clocked SR flip-flop and explain its working | (6 marks) |
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| | b. | Give short notes on the following: i)Fringing Capacitanceii)Skin Effect | (6 marks) |
| 8. | a. | With an example, explain how you will implement a monostable sequential circuit. | (6 marks) |
| | b. | Give the basic Rules in Stick diagram. Draw the Circuit diagram and its Stick diagram of 2 input Depletion mode NMOS NOR Gate. | (6 marks) |
| 9. | a. | Implement a 6 transistor CMOS SRAM cell. Explain its Read and Write operations. | (6 marks) |
| | b. | Give the significance of MOSFET scaling. Briefly explain Constant Field scaling used in MOSFET. | (6 marks) |
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